η^{6} Organometallic Hexagonal Boron Nitride: Functionalization and Properties

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Abstract

Hexagonal boron nitride (h-BN), renowned for its formidable attributes—tensile strength (~100 GPa), wide bandgap (~6 eV), high thermal conductivity (227-280 W.m⁻¹.K⁻¹), and chemical stability—poses a challenge in functionalization due to its electronegativity variance between boron and nitrogen.^{1,2} In a breakthrough, we present unprecedented organometallic functionalization via chromium carbonyl vapor exposure. This novel approach forms a pristine n6 bonding that preserves lattice planarity and interconnectivity between B- and N-centers, with the metal engaging each hBN ring. Computational analysis validates spontaneous surface reaction ($\Delta G = -35.50$ kcal/mol). Further, carbonyl groups seed silver nanoparticle growth, culminating in a conductive layer atop hBN. Fourier transform IR spectroscopy, Raman Spectroscopy and X-Ray photoelectron spectroscopic techniques reveals the molecular reaction mechanism involved in this functionalization. This non-destructive, chemically versatile functionalization ushers in a new era in multifunctional coatings, harnessing hBN's thermal and structural provess across diverse applications.

References

- [1] Golberg, D. et al. Boron nitride nanotubes and nanosheets. ACS Nano 4, 2010, 2979–2993.
- [2] Petrone, N., Cui, X., Hone, J., Chari, T. & Shepard, K. Flexible 2D FETs using hBN dielectrics. Technical Digest - International Electron Devices Meeting, IEDM, 2015, 19.8.1-19.8.4

Figures

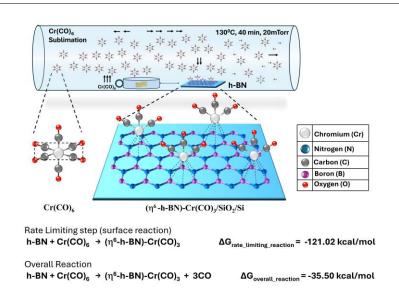


Figure 1: Schematics of h-BN functionalization with chromium hexacarbonyl (Cr(CO)₆) via chemical vapor deposition (CVD) in 1inch quartz tube.